

IN THE ABSTRACT:

Please cancel the current abstract and insert the following.

-- A projection exposure apparatus includes a projection exposure mask. The projection exposure mask includes a first mask pattern for exposing a member to form a continuous pattern thereon and a second mask pattern for exposing the member to form a discontinuous pattern thereon, one of the first and second mask patterns being a reflecting type mask and the other mask pattern being a transmitting type mask pattern, a projection system which projects light from the reflecting type mask pattern and light from the transmitting type mask pattern onto the member, a first illumination system which irradiates light to the reflecting type mask pattern from one side of the projection exposure mask, a second illumination system which irradiates light to the transmitting type mask pattern from the opposite side of the one side of the projection exposure mask, and a substrate stage which moves the member in a direction substantially orthogonal to a projection light axis of the projection system. --